Page 1 of 1 Form PTO-1449 U.S. DEPARTMENT OF COMMERCE ATTY. DOCKET NO. SERIAL NO. (MODIFIED) PATENT AND TRADEMARK OFFICE 039153-0448 (G1153) Unknown APPLICANT INFORMATION DISCLOSURE CITATION Lukanc et al. **GROUP ART UNIT FILING DATE** Unknown (Use several sheets if necessary) Unknown **U.S. PATENT DOCUMENTS FILING DATE DOCUMENT** SUB-**EXAMINER CLASS** REF DATE NAME 1F INITIAL NUMBER CLASS **APPROPRIATE** Α1 09/772,5277 Todd Lukano 01/30/2001 6,228,539 B1 05/08/2001 Wang et al. 430 5 **A2** 01/12/1999 430 5 5,858,580 Wang et al. A3 5,807,649 09/15/1998 Liebmann et al. 430 5 Α4 430 311 5,573,890 11/12/1996 Spence **A5** 430 1/20/2001 **FOREIGN PATENT DOCUMENTS** TRANSLATION **DOCUMENT** SUB-DATE COUNTRY CLASS REF NUMBER CLASS YES NO OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Levenson et al., "Improving Resolution in Photolithography with a Phase-Shifting Mask," IEEE Transactions **A6** On Electron Devices, Vol. ED-29, No. 12, December 1982, pp. 1828-36. Lin, B. J., "Phase-Shifting Masks Gain an Edge," Circuits & Devices, March 1993, pp. 28-35. **A7** DATE CONSIDERED **EXAMINER** EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conf rmance and not considered. Include any copy f this form with next communicati n t applicant.